



Electrochemical and Photocatalytic-Based Degradation Technologies for the Treatment of Emerging Contaminants

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Message from the Guest Editors

This Special Issue, entitled “Electrochemical and Photocatalytic-Based Degradation Technologies for the Treatment of Emerging Contaminants”, seeks high-quality papers focusing on the latest advances in electrochemical and photocatalytic technologies for the treatment of emerging contaminants. Topics include, but are not limited to, the following:

- Theory and mechanism of photocatalysis/electrocatalysis
- Design, analysis, control, optimization or operation of photocatalysis/electrocatalysis system.
- Treat of environmental emerging contaminants
- Research on advanced oxidation technology
- Catalytic materials and performance application
- Conservation of renewable energy
- Development and application of photocatalysis/electrocatalysis in industry





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Message from the Editor-in-Chief

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